Novascan PSD-UVT Decontamination System

The PSD-UVT was designed for applications in the electronic, semiconductor and scientific industries. A mercury vapor lamp generates ultra-violet light and ozone resulting in the atomic cleaning of silicon, silicon nitride, glass and other materials. The PSD-UVT can also be used for UV curing, UV patterning, sharpening AFM probes and ozone etching. Unit specifications appear below. A temperature controlled stage was designed to maximize the destruction of molecular organic materials. A digital controller with PID feedback loop accurately maintains stable temperatures of up to 150 degrees Celsius.

Features:

- The PSD-UV removes organic contaminants
- UV lamp generates UV light at both 185nm and 254nm
- Produces O3 and provides molecular excitation
- Operates at atmospheric pressure with ambient air or oxygen
- Multiple gas ports for the introduction of gases
- Adjustable sample to lamp distance
- Safety switched to prevent user exposure to UV light
- Temperatures of up to 150 degrees Celsius
- Simple operation and compact footprint